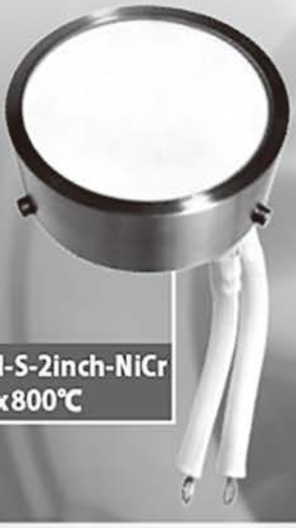
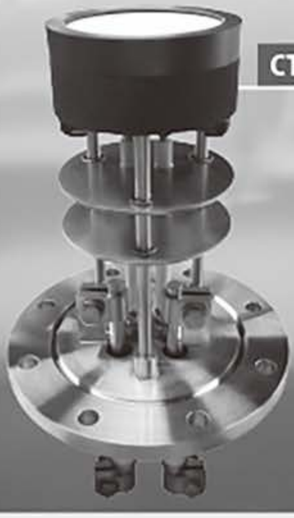
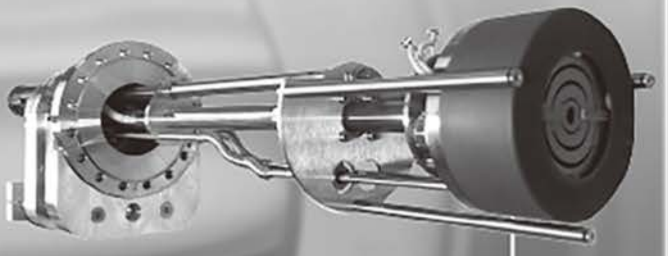
# Ceramic Top Heaters Max1800C



**CTH-S-2inch-NiCr Max800℃**



**CTH-F-3inch-SiC Max1800℃**



**HS-F-3inch-CCC Max1800℃**

## ● SUBSTRATE Heater for UHV thin film deposition

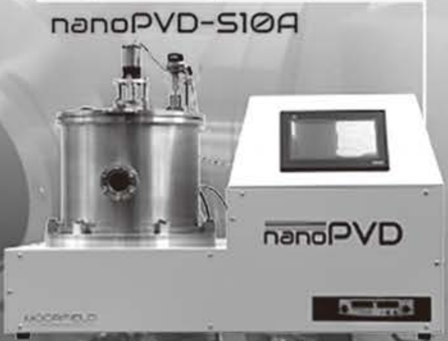
■【Ceramic Top Heater Max1800℃】 ■【Hot Stage】RF/DC bias, rotation & Z-shift

Heater stages for substrate heating, wafer heating and sample heating & manipulation

# Bench Top thin film deposition

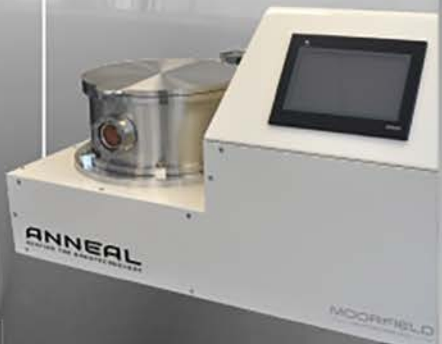
**Magnetron Sputtering**

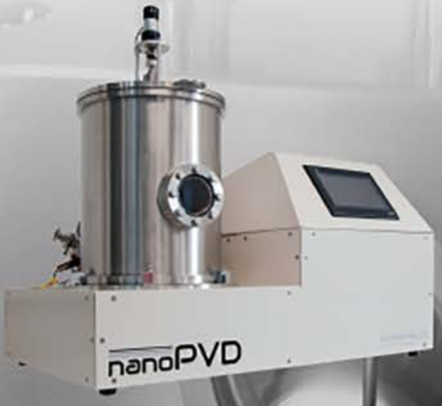
nanoPVD-S10A



**Benchtop Wafer Annealing**

ANNEAL





**Thermal evaporation for metal & Organic**

nanoPVD-T15A

## ● Benchtop thin film deposition series

■nanoPVD-S10A…3 sources for 2" targets, RF and DC PSU, 3 x MFC

■nanoPVD-T15A…2 for low temp evaporator, up to 2 sources for organics

■ANNEAL…Substrate annealing up to 1000 °C with precision atmosphere control

Thermocera endless possibility_thermal engineering

**Thermocera Japan Ltd.**
www.thermocera.com

Shin-Makicho Bldg Annex1_2F, 3-2-14 Nihonbashi, Chuo-ku Tokyo
Tel:03-6214-3033 Fax:03-6214-3035 E-mail:sales@thermocera.com